

ABSTRACT

Provided is a reflective mask blank capable of easily forming a fine mask pattern and less likely to cause reflective property deterioration of a multilayer reflective film during the production of a reflective mask.

- 5 The reflective mask blank includes a substrate, a multilayer reflective film to reflect EUV light, a protective film, an absorber film and a hard mask film stacked in this order, wherein the protective film contains more than 50 at% of at least one element selected from the group consisting of rhodium, palladium, iridium and platinum, and wherein the hard mask film contains ruthenium.